

Micro-Raman Spectroscopy Investigation of Hard Coatings

Dissertation
zur Erlangung des akademischen Grades
doctor rerum naturalium
(Dr. rer. nat.)

vorgelegt
der Fakultät für Naturwissenschaften der Technischen Universität Chemnitz-Zwickau

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geboren am 27.11.1966 in Bochum

Chemnitz, September 1997

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